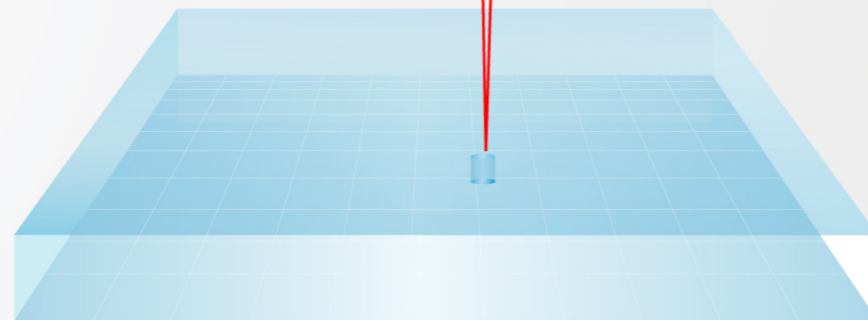
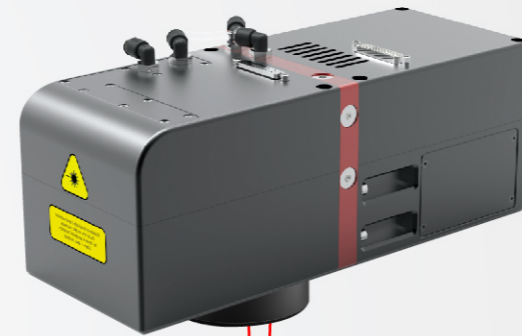


2.5D FE10(E10) / FE15(E15) / FE20(E20)

Support wavelength:355/532/1064nm

Deep engraving, small field micro processing
Priority choice for micro-processing

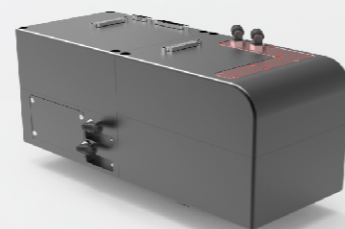
- CNC shell,dust prevention,compact structure,easy to integrate.
- Optional water cooling design, it can be applied to high-temperature drift requirements.
- Adopts the digital pulse width modulation driving technology, owns higher response speed and lower temperature drift.



E10



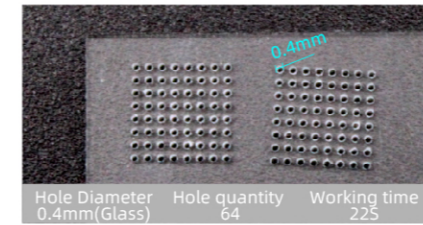
E15



E20

Highlight: drilling, high precision marking

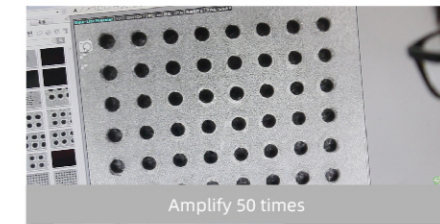
The Z-axis is responsible for adjusting the focal length of the center point, the Z-axis is fine-tuned to follow the depth change, and it can easily achieve high-precision work such as drilling.



Hole Diameter	Hole quantity	Working time
0.4mm(Glass)	64	225

High efficiency

The dynamic axis and the XY axis are fully software coordinated, and the layered focus compensation is completed in microseconds with high efficiency.



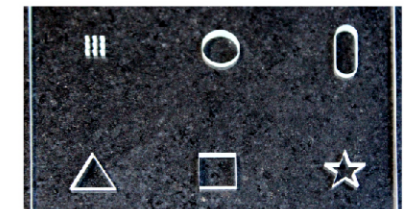
High precision

With the switch of the processing depth, the dynamic axis coordinately adjusts the focal length and adjusts the center spot in real-time, which can achieve higher accuracy than traditional scanhead.

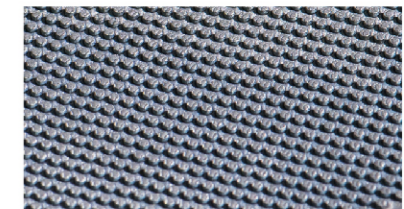
Application Highlight



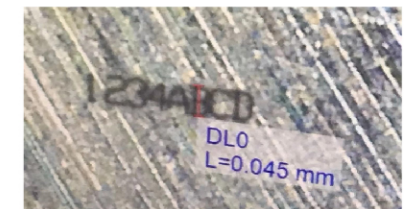
- Drilling
- Drilling
- Super precision marking



Glass drilling (different shape)



Hard material deep carving



Precision marking



Engraving (knife tool)

2.5D

FE10(E10) / FE15(E15) / FE20(E20)

Support wavelength:355/532/1064nm

Product Technical Information

Technical Info.		Specifications	
Items	Input Voltage(VAC)	100V60HZ / 220V50HZ	
	Output Voltage(VDC)	±15	
	Current(A)	4A (3 Sets)	
	Output Interface	XY2-100 Protocol	
	Input Interface	Communication interface USB	
Cooling Condition	Cooling Media	Distilled or de-ionized water plus corrosion inhibitor	
	Temperature(°C)	22-28	
	Recommended cooling pressure(bar)	2-3	
	Recommended flow rate(l/min)	4-6	

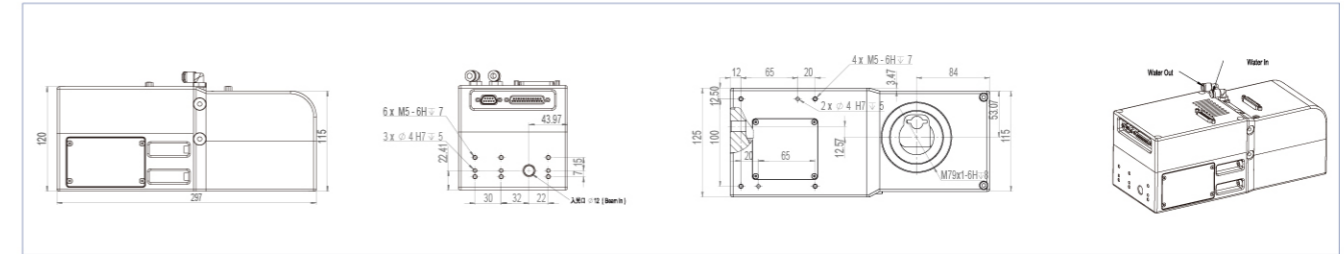
Product line	Product line	E10			E15			E20		
	Weight (KG)	5.6			6.7			9		
	Size(mm)	297x125x120			322x125x120			337x134x153.5		
Galvanometer Specifications	Version	Standard	Pro	P2	Standard	Pro	P2	Pro	P2	
	Tracking error (ms)	±0.18	±0.18	±0.16	±0.21	±0.21	±0.2	±0.28	±0.27	
	Repeatability(μrad)	8	8	5	8	8	5	8	5	
	Temperature drift(μrad/k)	<2	<2	<1	<2	<2	<1	<2	<1	
	Long-term drift (> 24h, room temperature)(mrad)	≤0.3	≤0.3	≤0.1	≤0.3	≤0.3	≤0.1	≤0.3	≤0.1	
	Max.processing speed (characters/s)(high-quality mode)	350 C/S@200×200								
	Operating temperature(°C)	25°C±10°C								

E10 Optical Specifications	Wavelength	355nm		532nm		1064nm	
	Input beam diameter(mm)	6.5mm (Customizable)		6.5mm (Customizable)		7.5/8.5mm (Customizable)	
	Input magnification options(μrad)	2、2.66		2、2.66		1.16	
	Aperture Size(mm)	10mm					
	Working Field&Z depth	Short focal depth version Working Field285±5;(f-θ f=254) Working Field190±5;(f-θ f=163)			Long focal depth version Working Field285±25;(f-θ f=254) Working Field190±25;(f-θ f=163)		

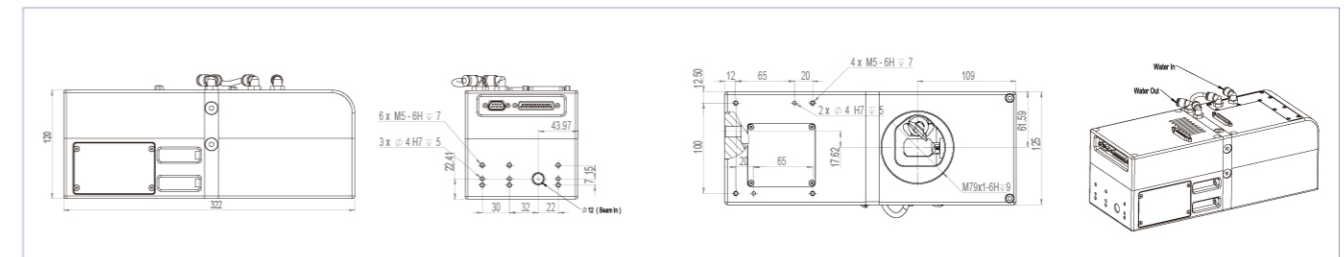
E15 Optical Specifications	Wavelength	355nm		532nm		1064nm	
	Optional beam expansion(μrad)	1.66X		2X		2.66X	
	Working Field&Z depth	f-θ 254Lens 100*100working field: ±5mm f-θ 254Lens 150*150working field: ±25mm		f-θ 163Lens 100*100 working field: ±10mm		f-θ 163Lens 100*100 working field: ±5mm f-θ 254Lens 150*150 working field: ±25mm	

E20 Optical Specifications	Wavelength	355nm		532nm		1064nm	
	Input beam diameter(mm)	6.5mm (Customizable)		6.5mm (Customizable)		7.5/8.5mm (Customizable)	
	Input magnification options(μrad)	2.66		2.66		2.1、2.57、2.66	
	Aperture Size(mm)	20mm					
	Working Field&Z depth	Short focal depth version Working Field285±7.5;(f-θ f=254) Working Field190±7.5;(f-θ f=163)			Long focal depth version Working Field285±50;(f-θ f=254) Working Field190±50;(f-θ f=163)		

E10



E15



E20

